

High-Performance 5LPE Implementation Next-Generation Arm “Hercules” CPU

Kevin K. Yee (Samsung), Fakhruddin Ali Bohra (Arm), Edson Gomersall (Cadence)
Arm TechCon 2019
San Jose
Oct. 9, 2019

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High-Performance 5LPE Implementation Next-Generation Arm “Hercules” CPU

Kevin K. Yee
Marketing Director, IP & Ecosystem
Samsung Foundry

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Cadence, Arm, Samsung Foundry Partnership

**Collaboration
+
Customers
=
Innovation**

Cadence, Arm, Samsung Foundry Collaboration

Enabling the Next Level of Innovation

SAMSUNG

Leading Edge Process Technology – 5LPE

arm

Processor and Library IP – “Hercules” CPU

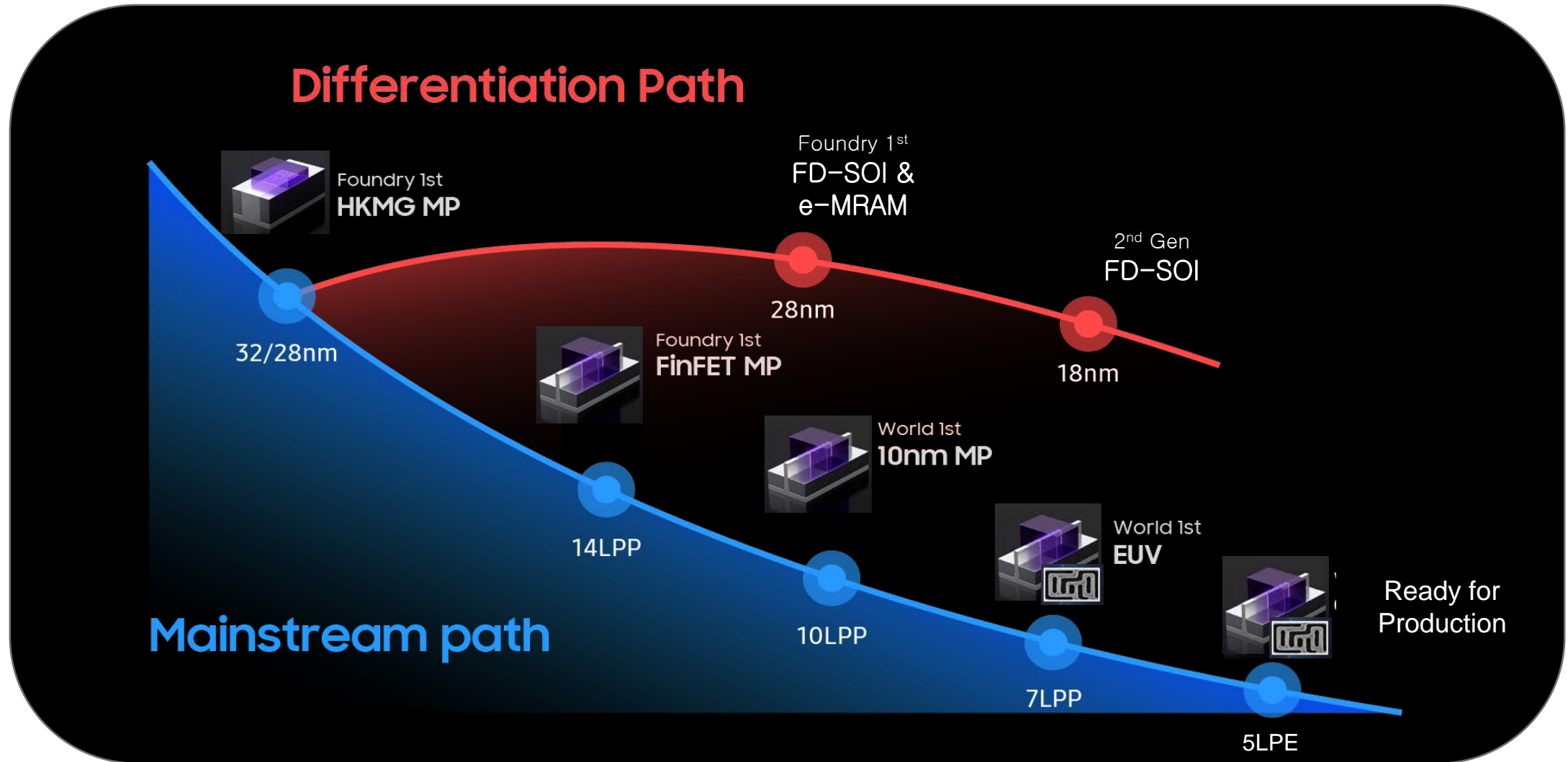
cādence[®]

EDA Tools & Flows – Tuned Implementation

Delivering the Most Optimized High-Performance Solution!

Samsung Foundry Technology Leadership

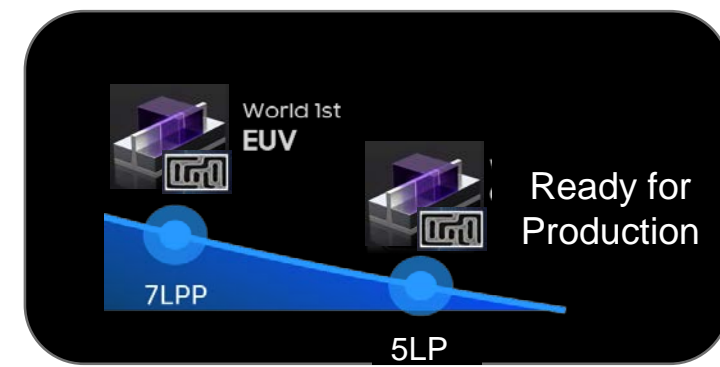
Leading the industry with many 1st



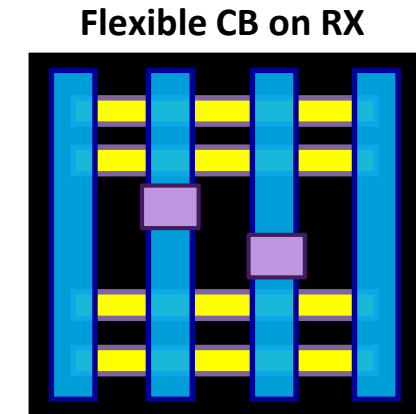
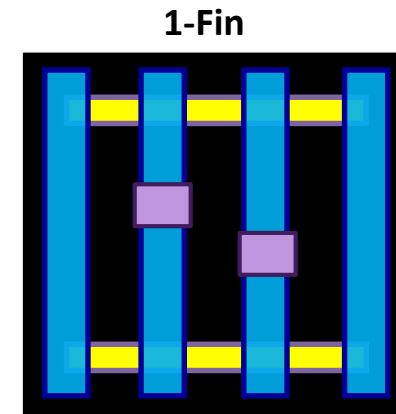
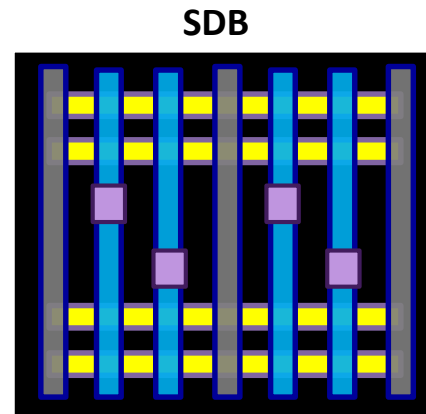
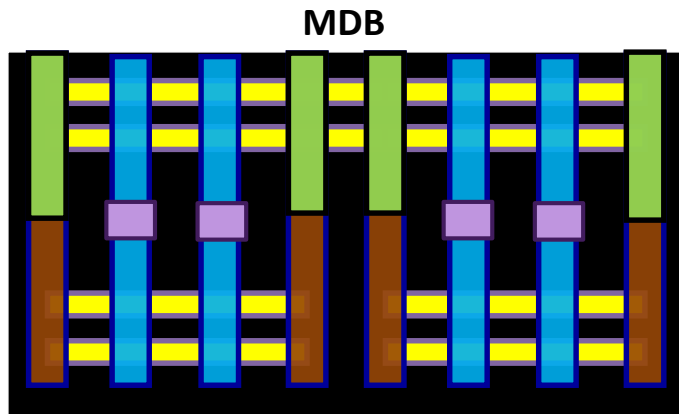
Why 5LPE?

Full EUV technology – ready for production

- 🌐 2nd gen. EUV technology
- 🌐 7LPP compatibility: IP re-use, yield leverage, easy migration
- 🌐 Enhanced features to 7LPP: MDB, SDB, single fin cell, CB on RX edge



Smart Scaling



5LPE Process Overview

Easy migration from 7LPP

IP re-usability with boosted transistor performance

- GR compatibility, same SRAM, same TR structure
- 1.11x perf boosted by Low-k spacer, DC enhancement, etc.

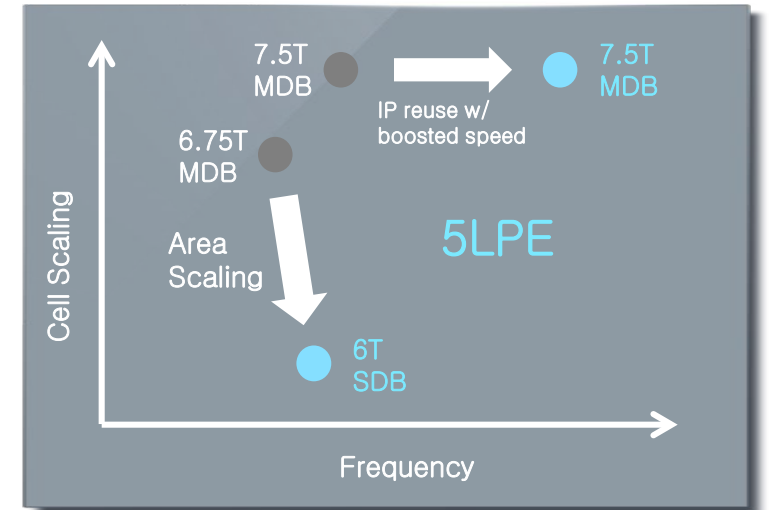
Smart scaling with 6T SC offering

- 0.70x block-level area due to 6T with SDB and CB on RX edge

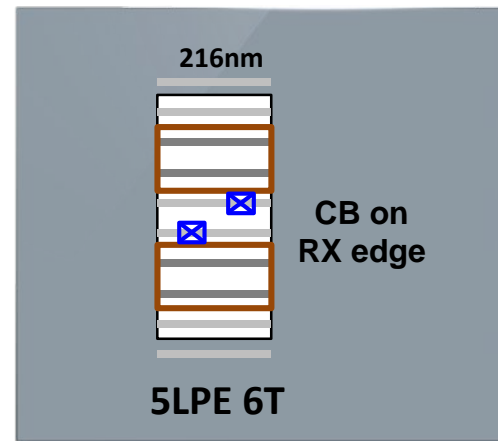
Superior power efficiency by 6T SDB with 1-Fin

- 0.80x block-level power

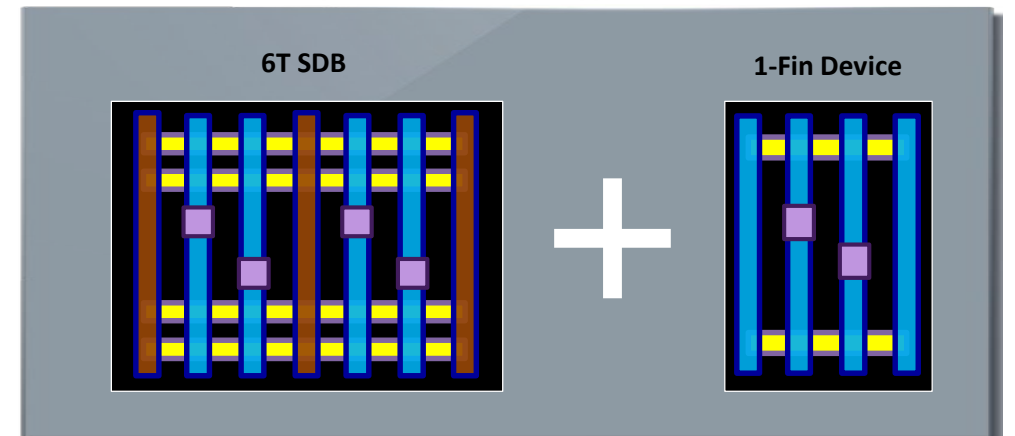
Migration Enhancement



Lower track standard



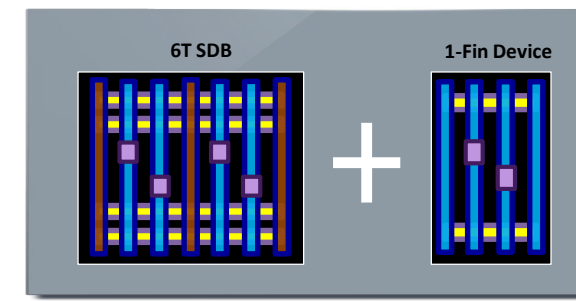
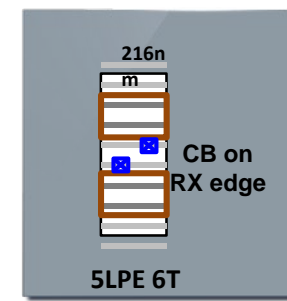
Superior power efficiency



5LPE Technology Enhancements

Enabling 36M2, SDB, 1FIN, CB on RX-edge & 6T

🌐 IP re-usability with boosted performance

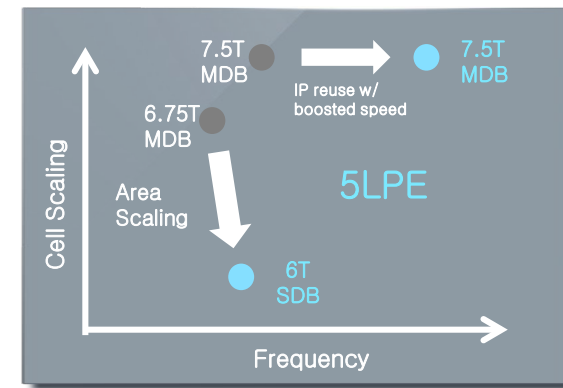


	7LPP	5LPE	Note
FP	27FP		Compatible
CPP	54CPP/60CPP		Compatible
SRAM bitcell	P026/P032		Compatible
Vop, Vth, Lgate	0.75V, RVT/LVT/SLVT, 8nm/10nm		Compatible
M1/M3/M4	40nm/36nm/44nm		Compatible
M2	48nm	+ 36nm	Enhance
Diffusion Break	MDB	+ SDB	Enhance
Min NFIN	2FIN	+ 1FIN	Enhance
CB	CB on STI	+ CB on RX-edge	Enhance
Standard Cell	7.5T	+ 6T	Enhance

5LPE Key Feature Comparison

7.5T for performance, 6T for area & power

- 7.5T: Performance driven with 60CPP and MDB
- 6T: Area & power driven with CB of RX edge, SDB and 36M2

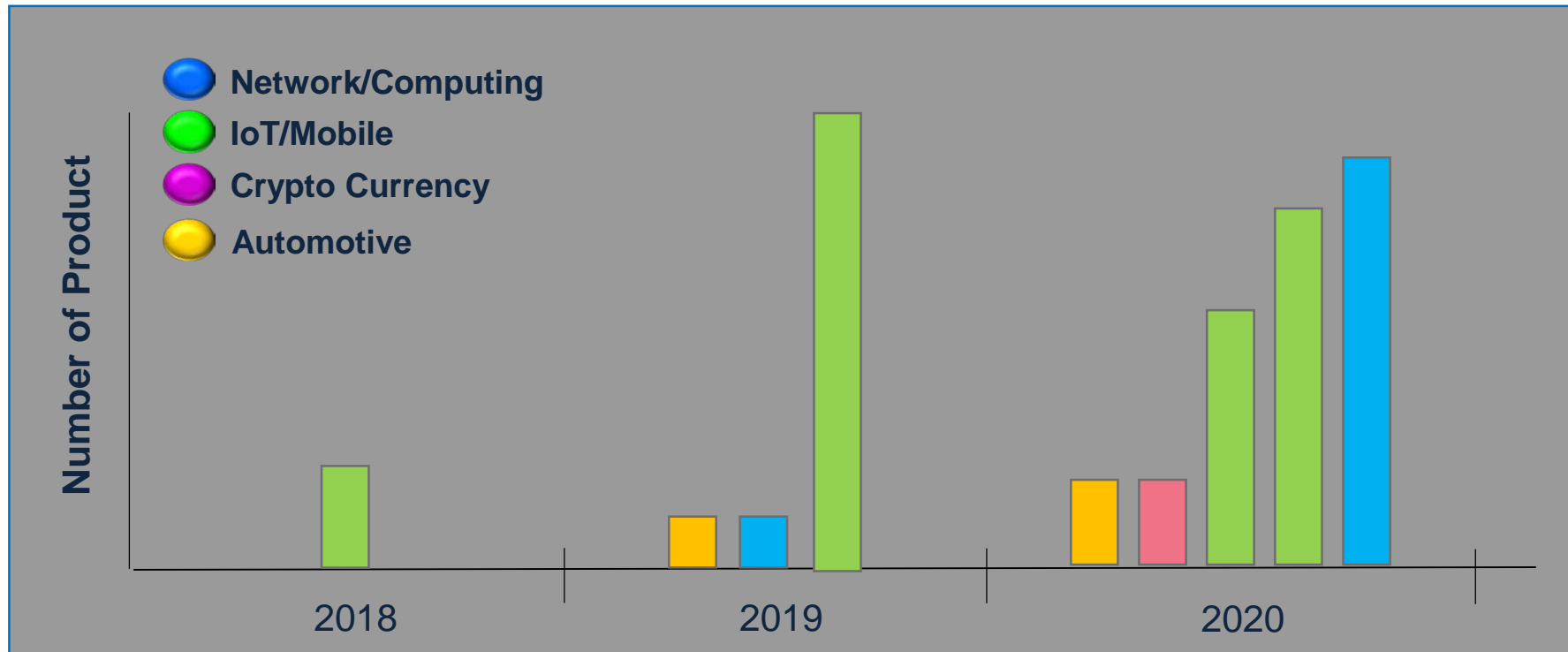


Track		7.5T [HD]	6T [UHD]
Cell Height [nm]		270	216
Tech Definition	FP [nm]	27	27
	CPP [nm]	60	54
	M1 [nm]	40Bi	40Uni
	M2 [nm]	60	36
	DB	MDB	SDB
	CB	CB on STI	CB on RX edge
Design Feature	FIN #	3:3	2:2
	Signal Track	6	5

5LPE Broad Market Adoption

7.5T for performance, 6T for area & power

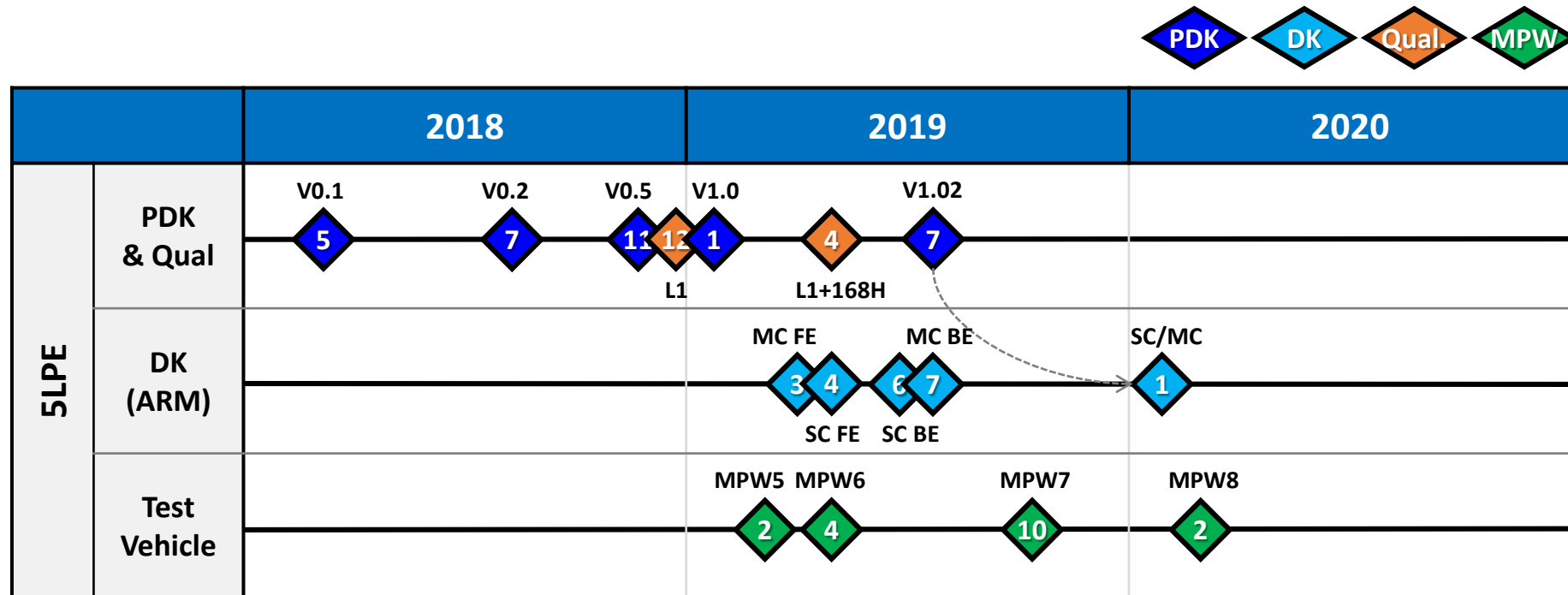
- 🌐 2018: 7nm production tapeout
- 🌐 2019: 5nm production tapeout
- 🌐 2020: Main node will be 5nm



5LPE Availability

Key milestones

- 🌐 PDK v1.0: Released Jan'19
- 🌐 L1+168H: Completed Apr. '19
- 🌐 MPW MTO: Feb'19



Samsung Advanced Foundry Ecosystem

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BOLD SILICON FUTURE**

OCTOBER 17, 2019
SAMSUNG@FIRST CAMPUS
SAN JOSE CA
9AM-7PM

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9am – 7pm
October 17, 2019
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REGISTER NOW!:

<https://events.samsungatfirst.com/foundry-safe-forum-2019/>

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The ARM logo is displayed in a large, white, lowercase, sans-serif font. It is centered horizontally against a dark blue background that features a faint, glowing grid pattern of light blue lines. The grid lines are slightly blurred and have a soft glow, creating a sense of depth and technology.

High-Performance 5LPE Implementation Next-Generation Arm “Hercules” CPU

Fakhruddin Ali Bohra
Senior Principal Design Engineer
Arm

arm

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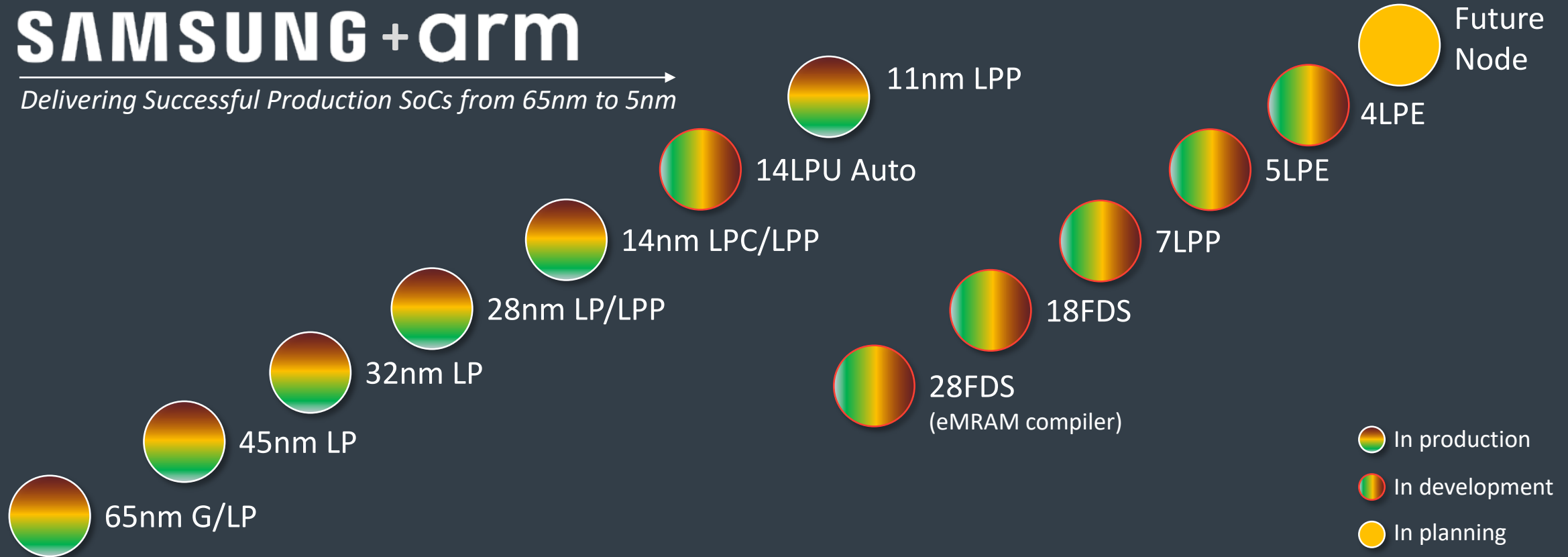
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Arm Artisan Physical IP and Samsung Foundry Partnership

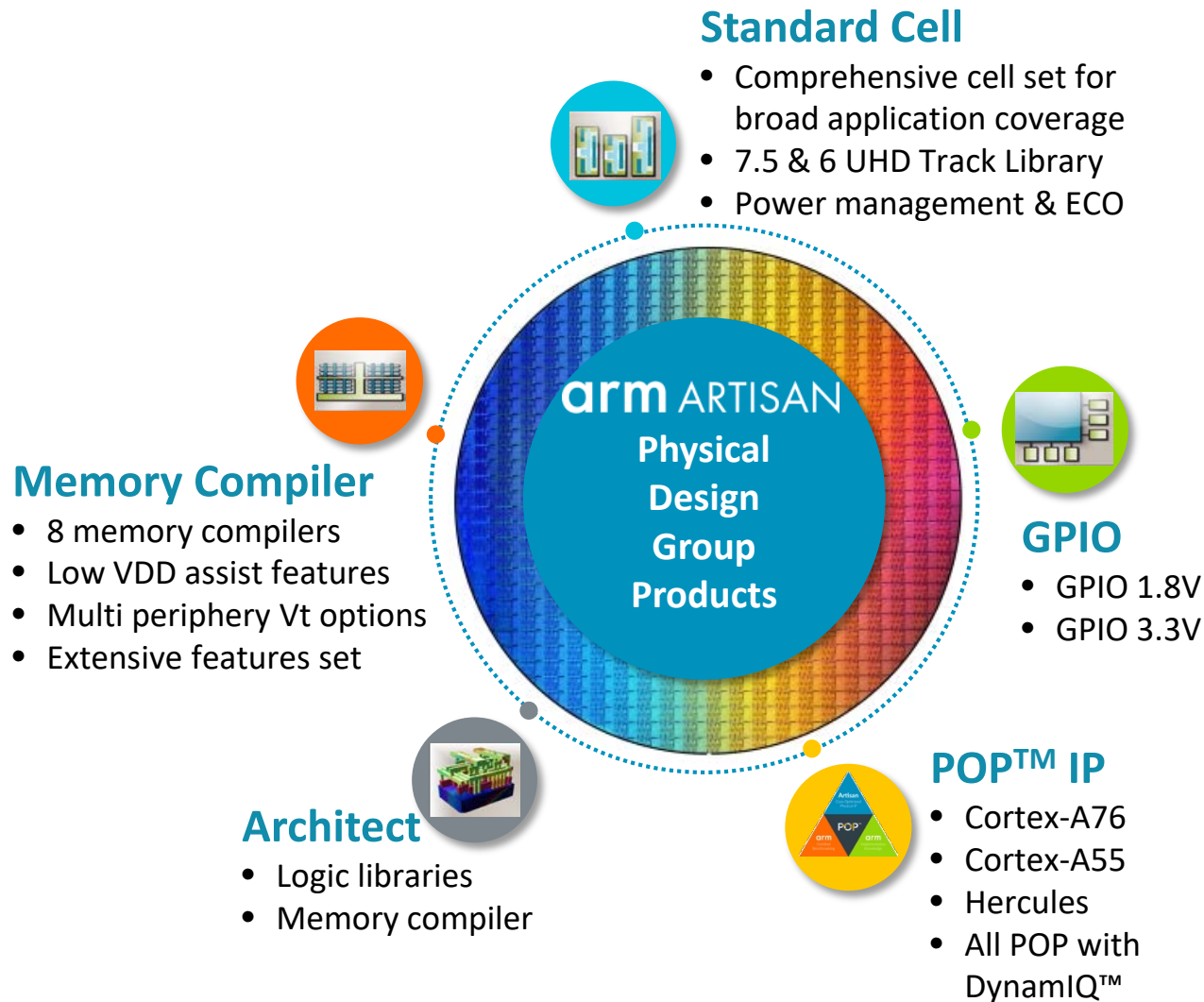
Over 3 billion chips shipped with Arm Artisan Physical IP

SAMSUNG + arm

Delivering Successful Production SoCs from 65nm to 5nm



Arm Artisan on Samsung Foundry 5LPE (EUV) Platform



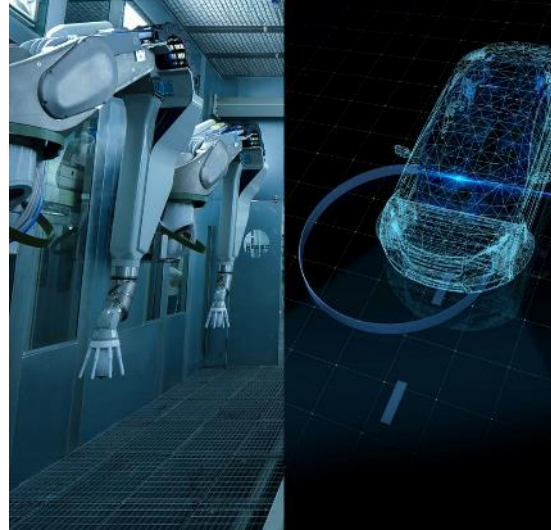
Complete Physical IP Platform

- Foundry sponsored foundation IP
Support wide range of applications from mobile, consumer and automotive
- POP IP for “Hercules” CPU, Arm® Cortex®-A76 and Cortex-A55 based computing systems
- Design kits available

Technology Trends that Will Redefine All Industries



Artificial Intelligence in every device



Autonomous machines



Augmented reality



Hyperscale cloud and connectivity

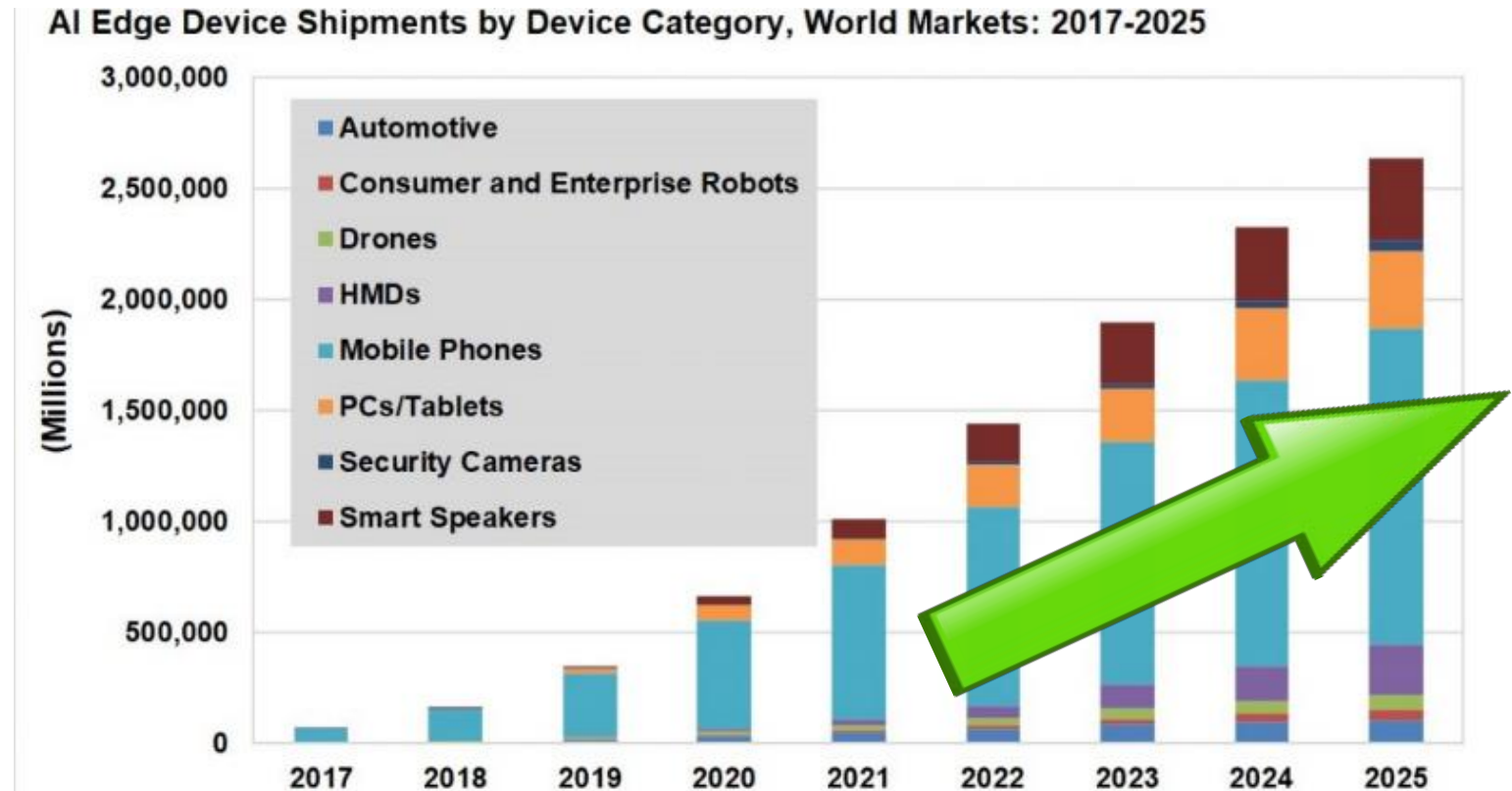


Security and Privacy

AI is Everywhere

Industry landscape: What trends will drive the industry

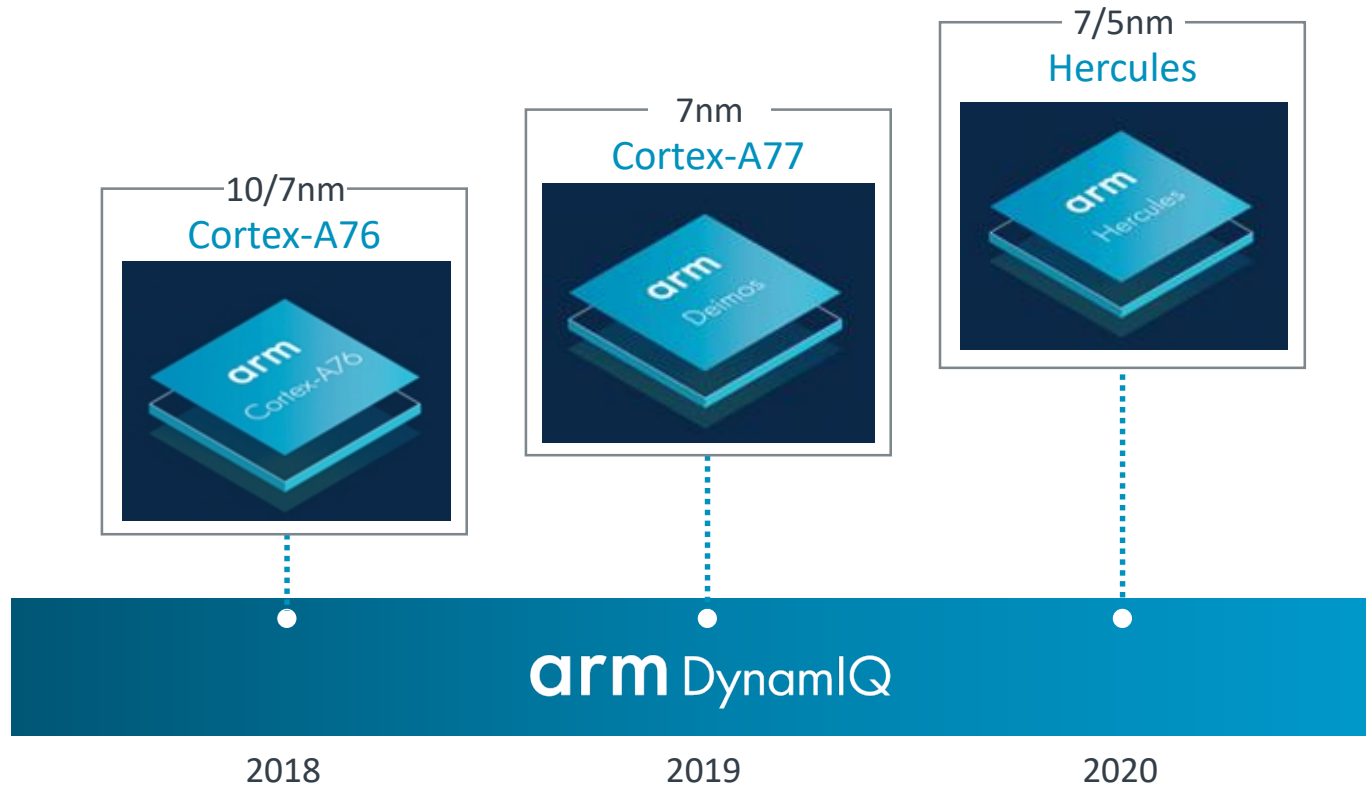
- AI cuts across applications spaces
- Projected continued growth across all applications



Source : Tractica (2018)

Breakthrough Performance for Always-On, Always-Connected

Continuing the trajectory of increased compute performance for AI, ML and premium mobile

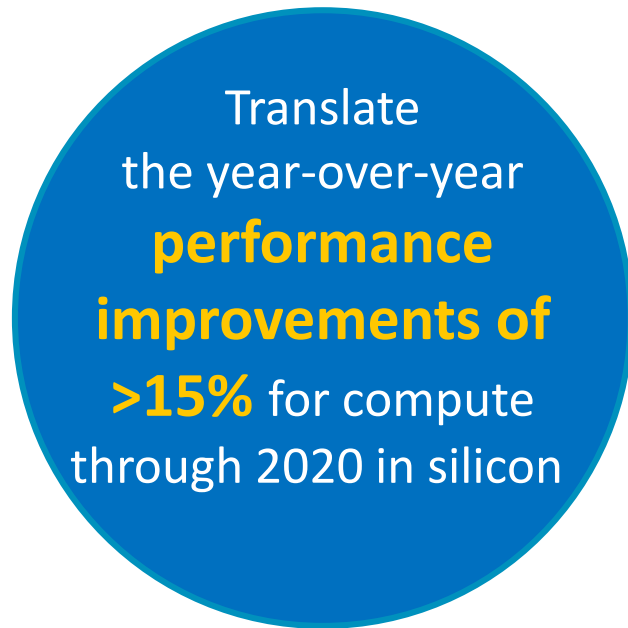


arm CORTEX-A

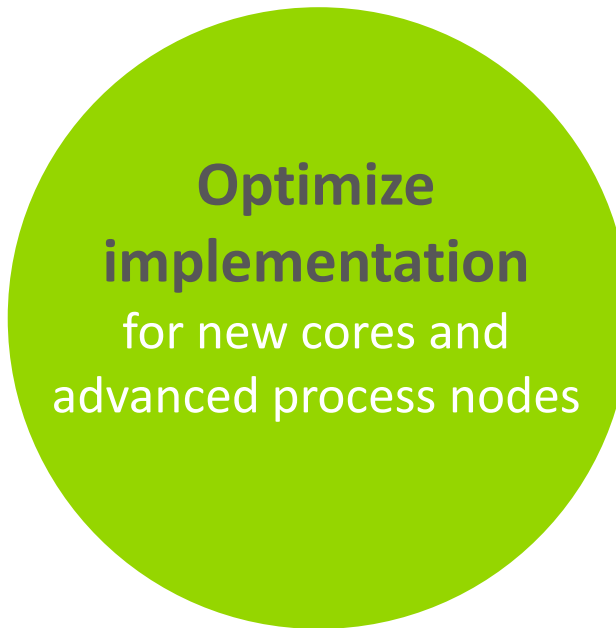
- ✦ **Cortex-A76: High-performance implementation: 3+ GHz in 7nm**
- ✦ **Cortex-A77: Up to 20% improved IPC performance**
- ✦ **Hercules: Continuing performance and efficiency leadership**
- ✦ **Supports the flexibility of Arm DynamIQ big.LITTLE™**

Translating Arm RTL Benefits into Silicon

HOW TO



?



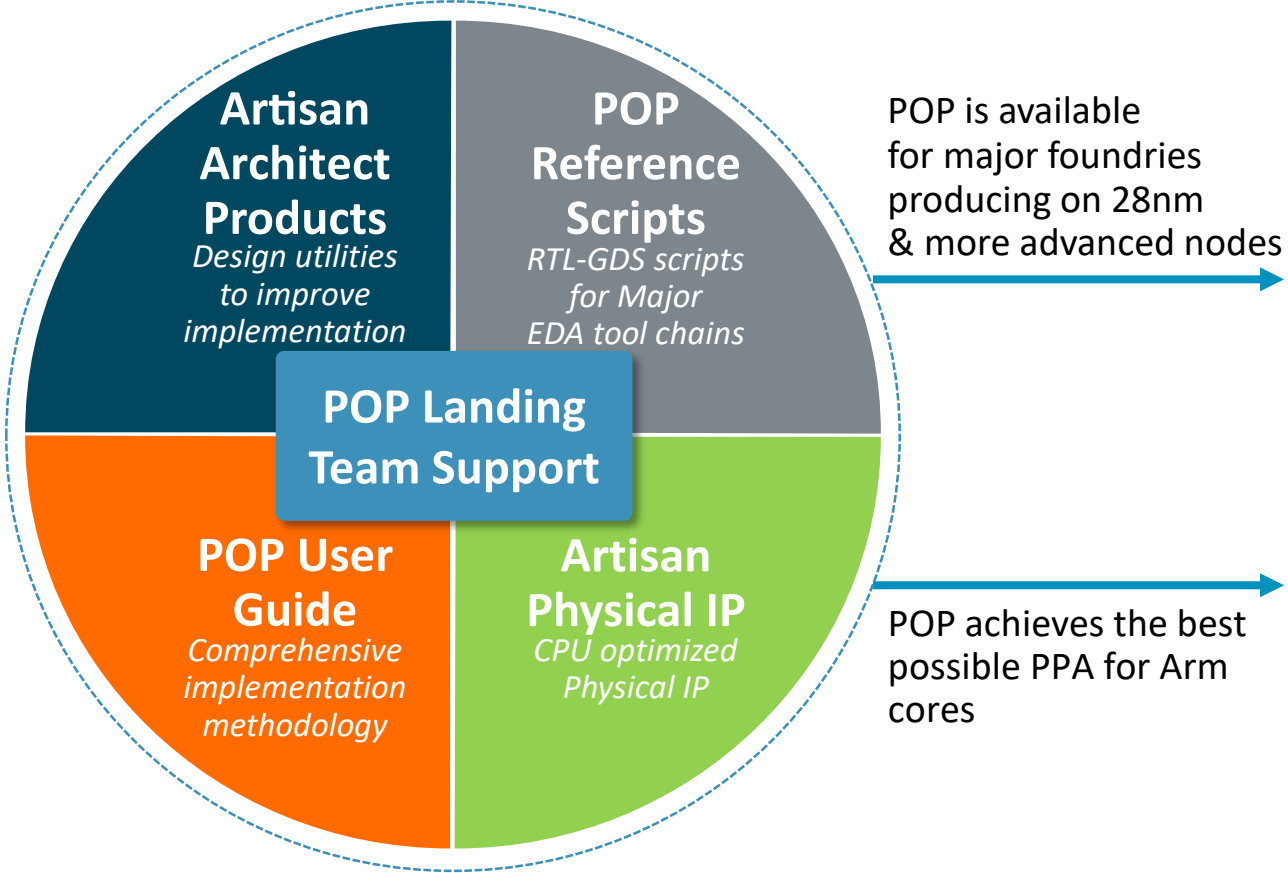
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Arm POP IP is Optimized Arm Core Implementation

POP IP Components



SAMSUNG FOUNDRY
and other foundries

- arm NEOVERSE
- arm CORTEX-A
- arm MALI
- arm ARTISAN

Comprehensive support and services

Design Technology Co-Optimization (DTCO) Benefits the Ecosystem

Lead Partner

Co-development work and design development
Transferring knowledge of 5LPE, Cadence Flow, "Hercules" RTL, Artisan physical IP and POP IP

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Alignment of Arm and Cadence product developments and process may vary by process maturity; iterative references may vary

Implementation Challenges

Challenges present for advanced nodes and cores

Advanced nodes

14nm

- FinFETs
- Placement rules
- DPT-aware colorless routing

5nm

- Via ladders
- New placement rules
- Power grid challenges
- Addressing variation

Latest Arm Cores

- Concurrent configuration of CPU with DynamIQ Shared Unit (DSU)
- Asynchronous configuration
- Long channels between DSU and CPU slaves
- Private L2 cache
- Architectural clock gating

5LPE: Continued Enhancements for Artisan Logic IP

Performance

- New compressor cells
- New flip-flops: 30% performance gain per cell level

Power

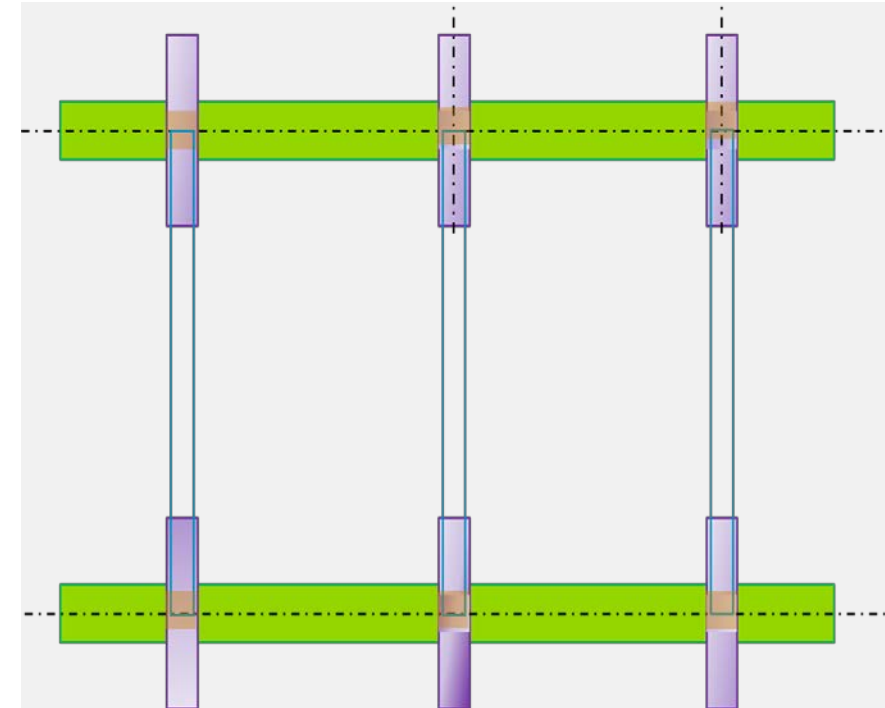
- New multi-bit functional cells
- Low power flip-flops

Density

- Key combinatorial cells: 5-10% area gains per cell level
- Flip-flops: 10+% area gains per cell level

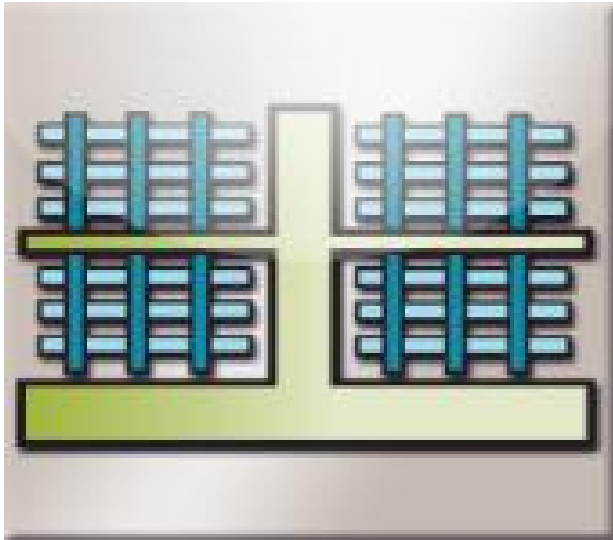
Implementation

- Cells crafted to enable flexible cell placement while maintaining a tight and regular lower grid
- Utilities included to ease power grid generation
- Post-route opportunistic M2 stitching supported to improve EM/IR drop
- Large clock drivers for ideal H-Tree implementation
- Power gate design ensures no break in grid regularity



Dependencies exists between standard cell architecture & power grid;
Proper grid required for optimization

5LPE: Continued Enhancements for Artisan Memory IP



Performance

- Special optimization for key compilers
- Bitcell selection to match 5LPE target markets
- Multiple level shifting options for optimized DVFS at SOC level
- Careful wireplaning to mitigate RC

Power

- Compile-time options for core and periphery separation, control, retention and power down
- Multiple architecture and micro architecture changes

Density

- Extensive MUX, bank and slice options
- Innovative assist scheme
- Newer topological options

Implementation

- Instance layout minimizes placement and abutment restrictions

The Cadence logo is displayed in a white, lowercase, sans-serif font with a registered trademark symbol (®) at the end. It is centered against a dark blue background that features a faint, glowing grid pattern and a perspective view of a circuit board or a similar technical structure.

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The section header is presented in a white, sans-serif font on a dark blue background. A vertical red bar is positioned on the left side of the text area. The text is left-aligned and reads: "High-Performance 5LPE Implementation Next-Generation Arm 'Hercules' CPU".

High-Performance 5LPE Implementation
Next-Generation Arm "Hercules" CPU

Edson Gomersall
Product Engineering Architect
Cadence

The Arm logo consists of the word "arm" in a lowercase, blue, sans-serif font.

arm

The Samsung Foundry logo features the words "SAMSUNG" and "FOUNDRY" stacked vertically in a blue, uppercase, sans-serif font.

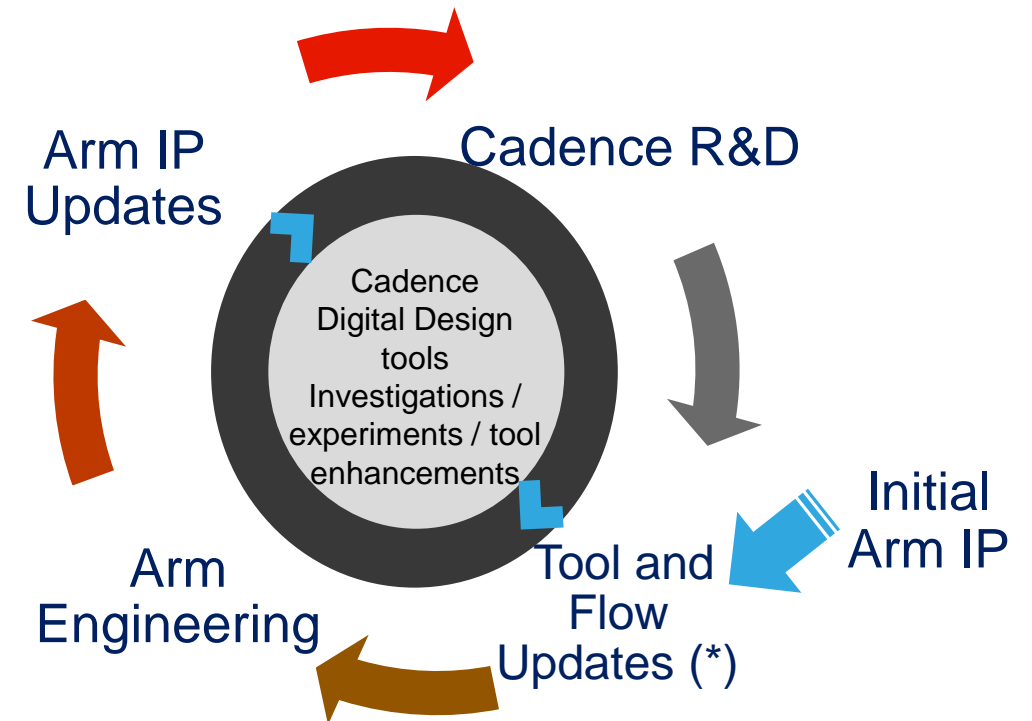
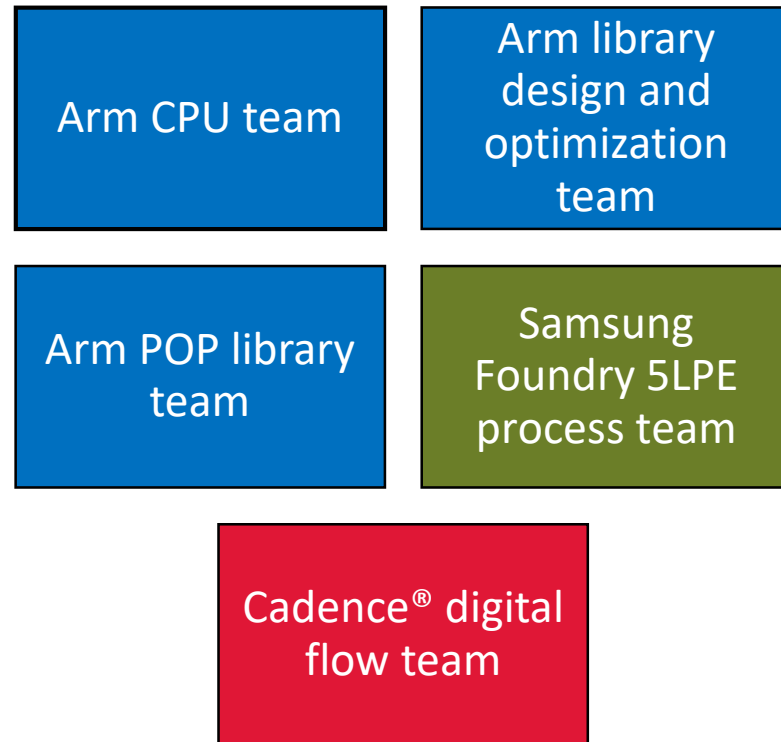
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The Cadence logo is shown in a lowercase, black, sans-serif font with a registered trademark symbol (®) at the end. A small red horizontal bar is positioned above the letter 'a' in "cādence".

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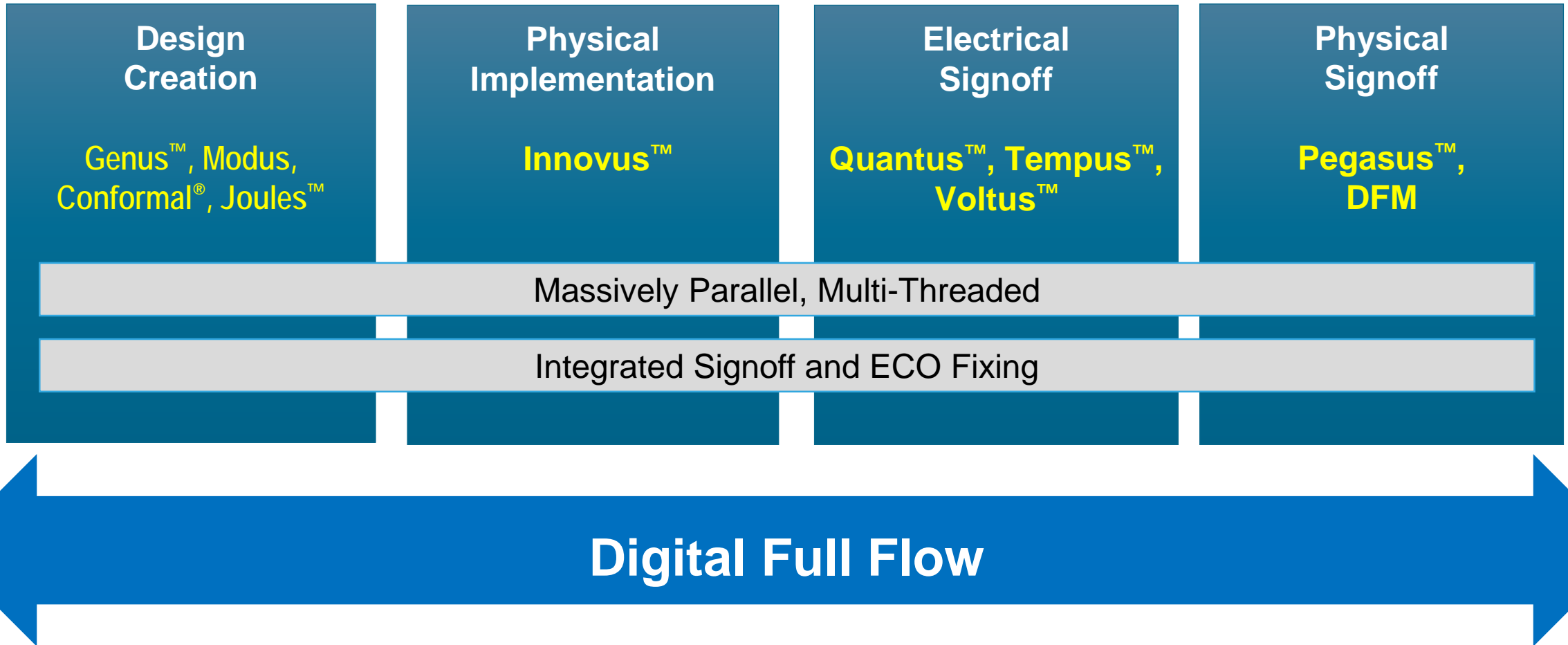
Cadence, Arm, and Samsung Foundry Collaboration

- Worldwide engineering relationship



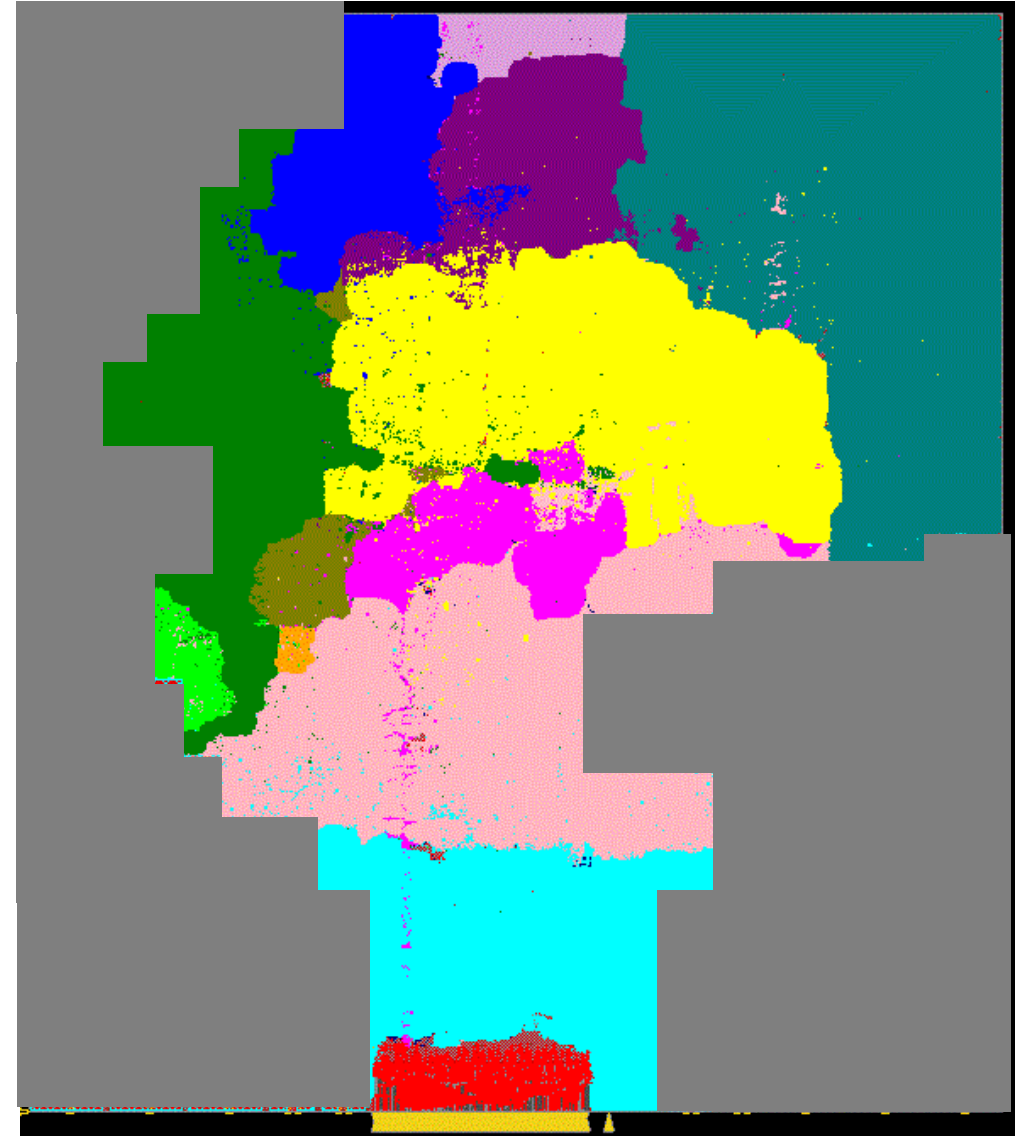
- Collaboration enables high-performance flow to be delivered
() Early collaboration ensures tool support in place*

Arm CPU 5LPE Digital and Signoff Flow



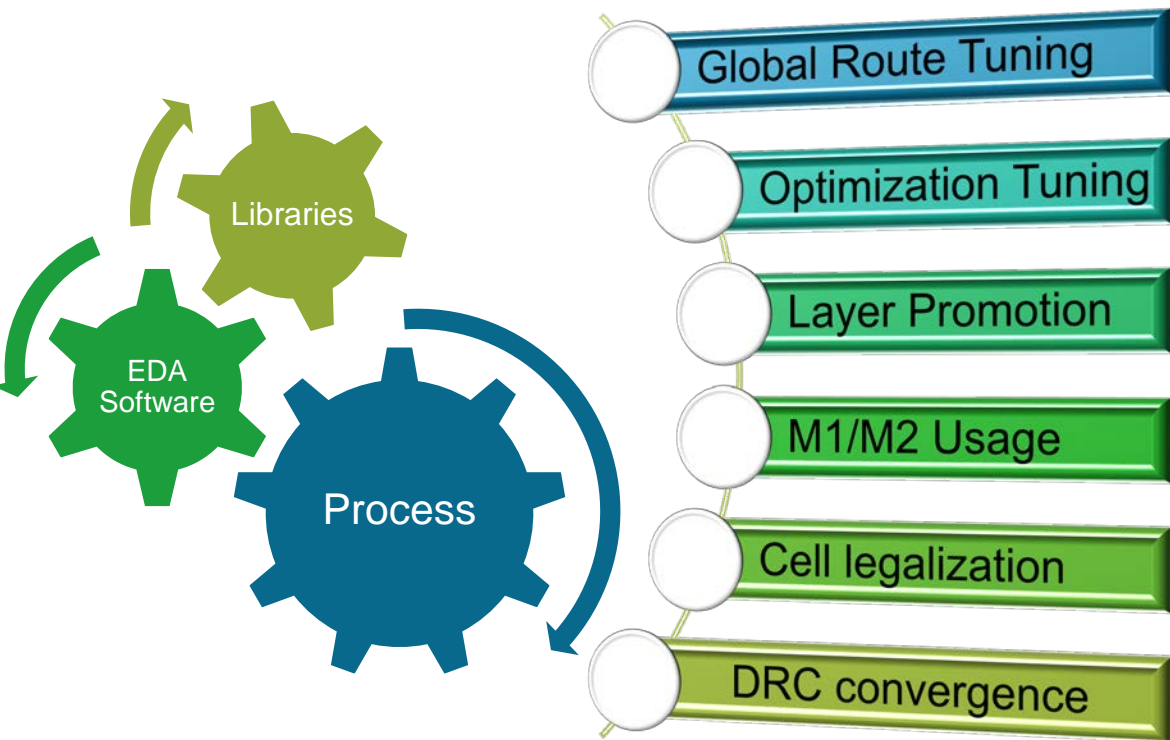
Arm CPU 5LPE Design Configuration

- Process
 - Samsung Foundry 5LPE
 - 13 Layer Metal stack
- CPU Core Overview
 - Arm CPU 5LPE POP 7.5T standard cells
 - Arm CPU 5LPE POP FCI memories
 - Arm CPU floorplan
- Multiple voltage islands



Cadence and Samsung Foundry 5LPE Co-Optimization

5LPE Process and Tool Co-Optimization



- One simple option to enable all 5LPE process support

```
setDesignMode -process 5 -node s5
```

Metric	After eGR tuning
Frequency	14% improvement
Utilization	7% improvement

Early Global Route Tuning

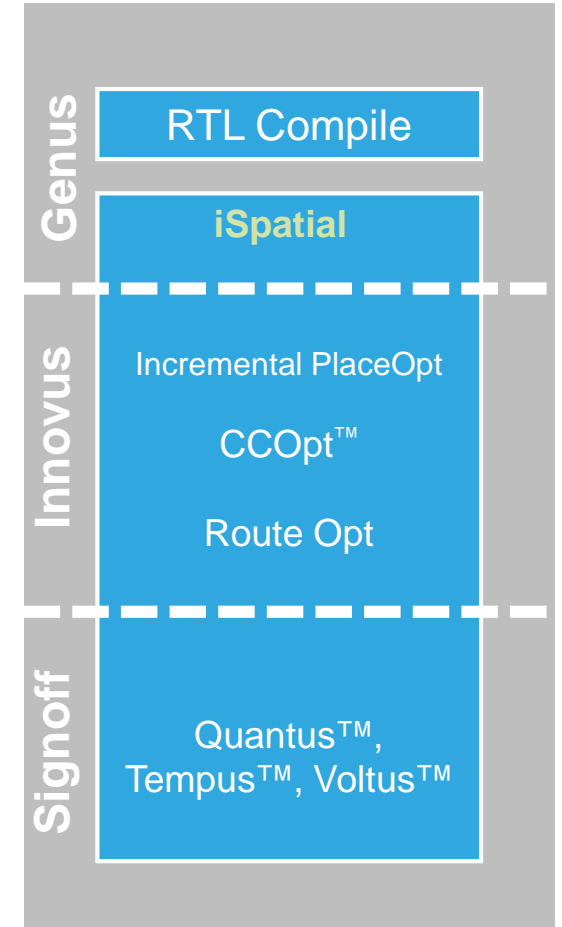
	M4	D5	D6	D7	D10
Before tuning	80.5	77.9	84.2	51.5	43.2
After tuning	81.4	79.7	85.5	52.7	61.3

Layer Promotion Adherence

Out-of-Box Better Full Flow PPA

5LPE and CPU Characteristic Driven Features

5LPE-driven features	CPU-driven features
Early global route tuning	Floorplan regions/guides
Layer promotion	ICG placement optimization
NDRs for specific layers	Custom cost groups
Cell legalization	Strategic pre-skewing
Statistical Via support	Clock tuning

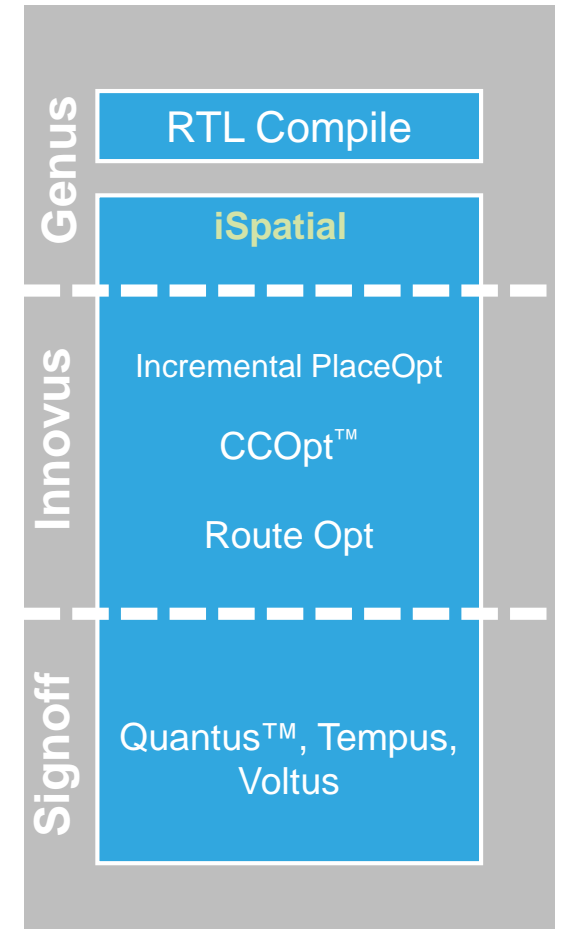


Cadence Digital Flow Benefits

- Combined Genus™ and Innovus™ solution with common optimization
 - **iSpatial** technology
 - **2x** TAT improvement, **5%** PPA benefit
- IR drop-aware flow
 - Integrated IR drop repair flow
- True signoff
 - Completely integrated with industry-leading Innovus Implementation System
 - **Tempus™** and **Voltus™** solutions combined is TRUE SIGNOFF
 - Via variation-aware timing signoff
- Stylus common UI
 - Usability and productivity enabler

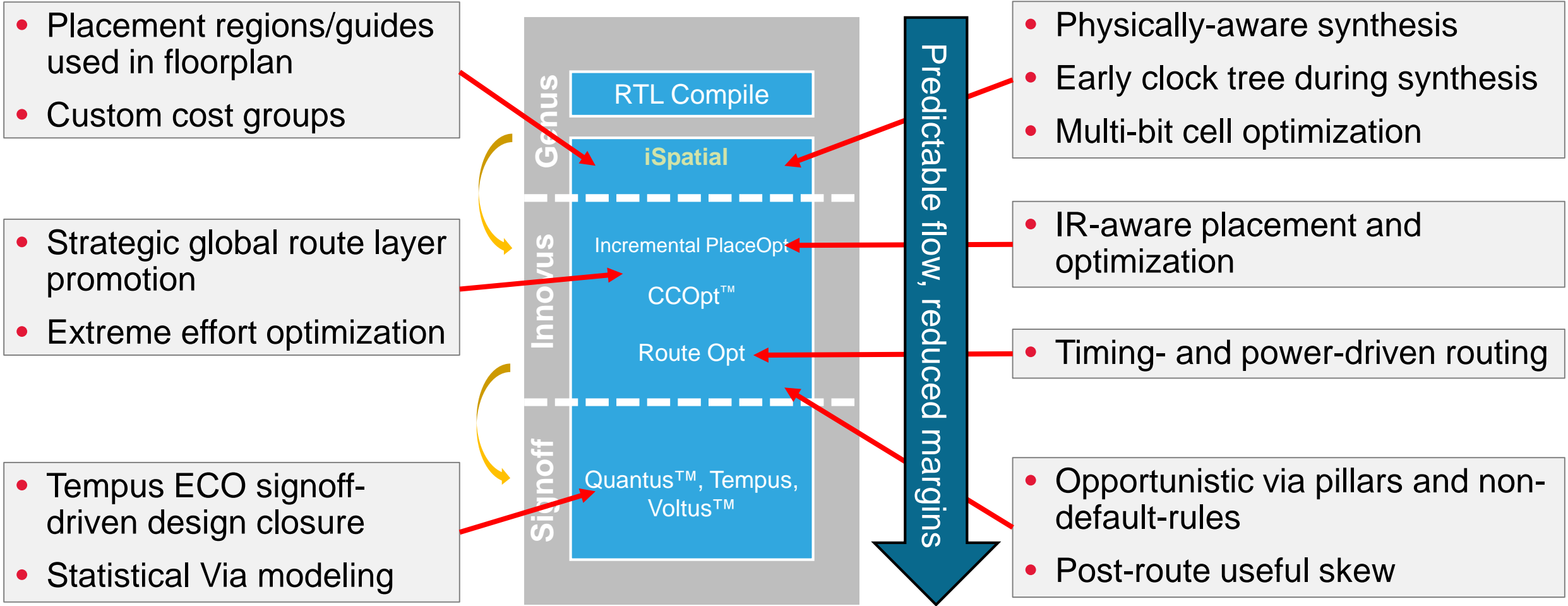
Correlation
with Physical

Correlation
with Signoff



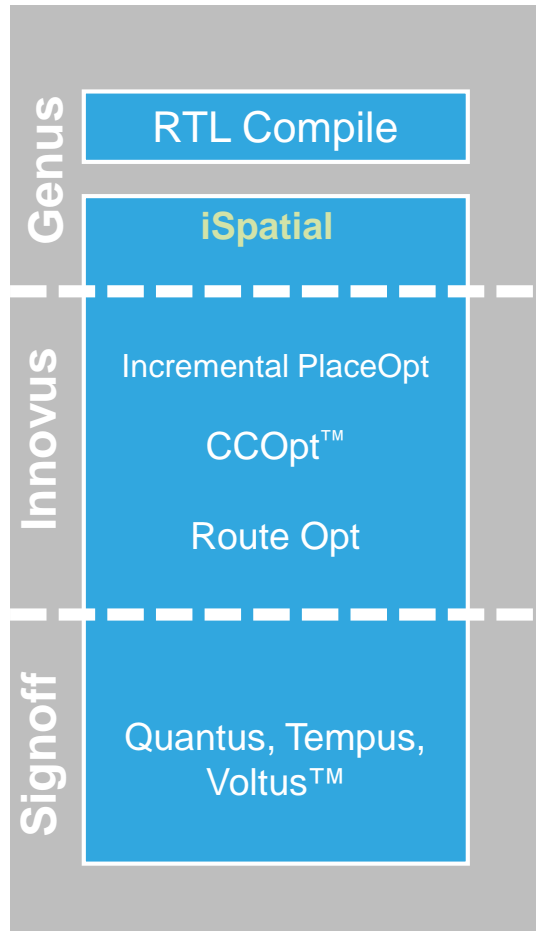
Arm CPU 5LPE iSpatial High-Performance Flow

Turn-around time and predictability benefits



Mesh and Flex-H clock distribution supported which can influence design performance

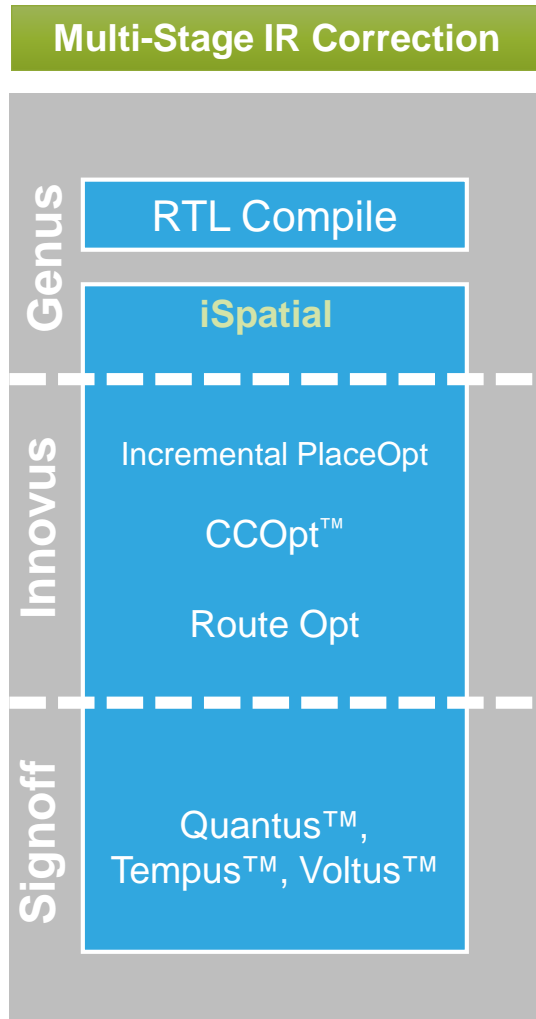
5LPE Statistical Via Timing Analysis and Optimization



- Exclusive feature used in 5LPE signoff flow
- Global Via resistance variation modelled in extraction technology files
- Local Via resistance variation is modelled statistically by the foundry
 - Samsung Foundry provides mean shift and standard deviation of via cut sizes
 - Quantus™ Extraction provides via resistance for each via
- Tempus™ delay calculation engine uses both global and local resistance variation to ensure timing convergence during the flow
 - Part of the Samsung Foundry 5LPE signoff requirements
- Tempus ECO optimization accounts for all Via resistance effects

Concurrent Timing, Power, and IR Drop Optimization

Innovus, Tempus, Voltus single data model integration



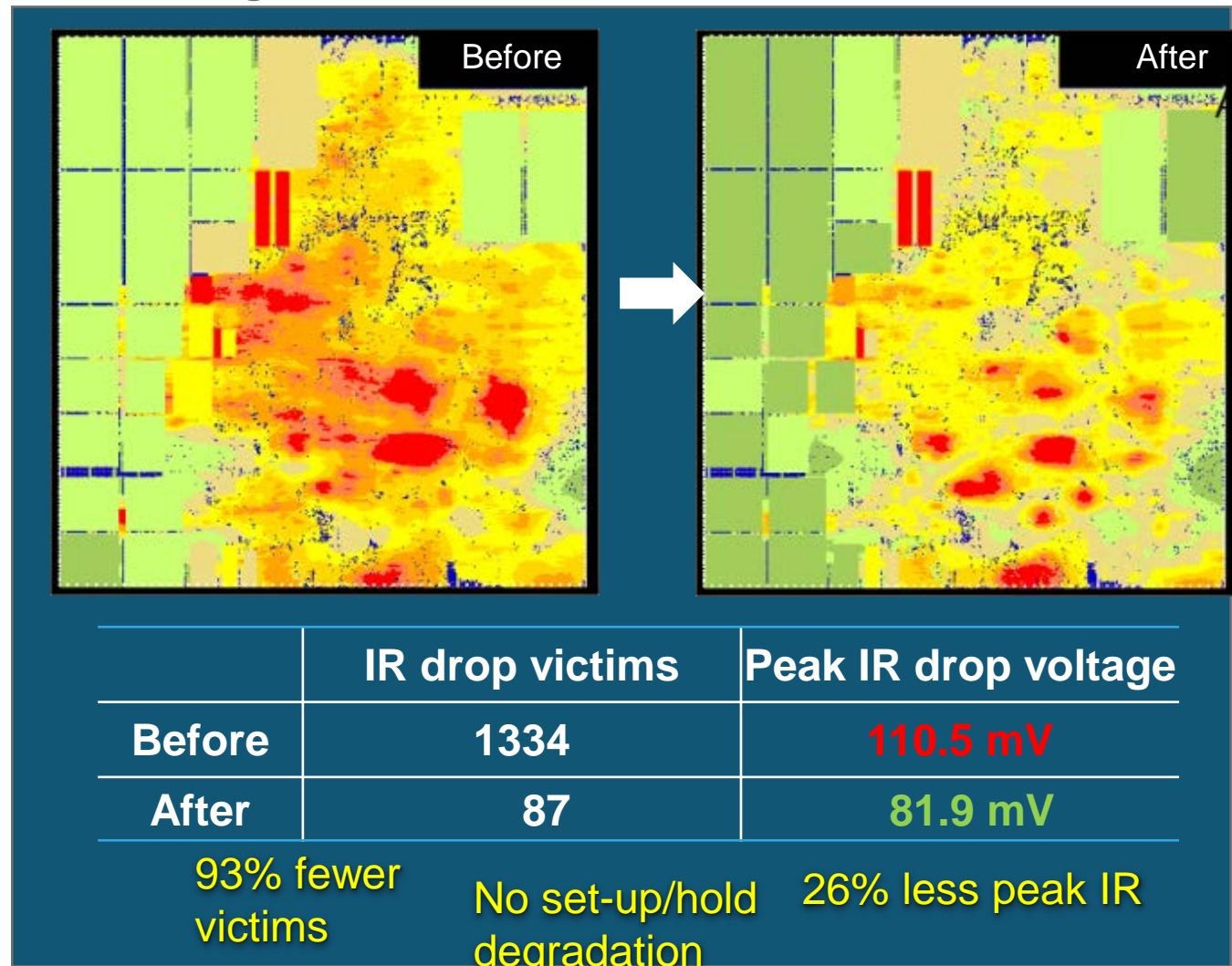
Early Rail Analysis

IR Drop-Aware Placement

Clock Useful Skew for Peak Power

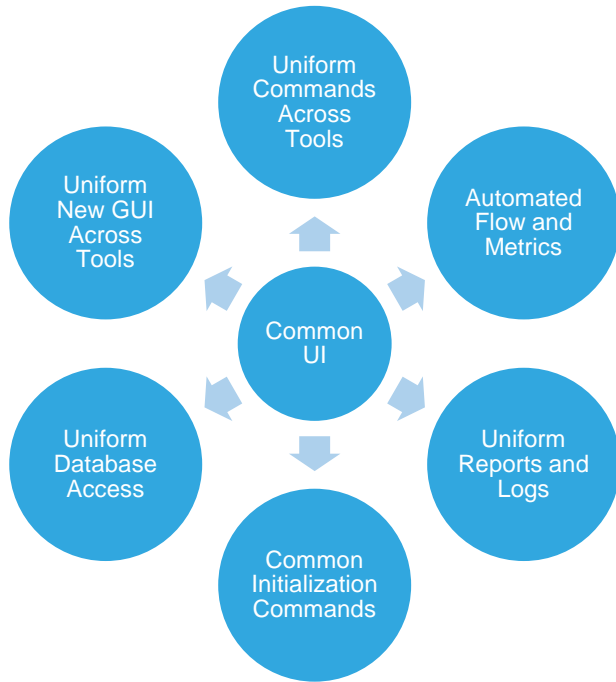
Power Routing and Via Optimization

Timing And IR Drop-Aware ECO



Full-Flow Unified Interface and Flow for Digital Implementation

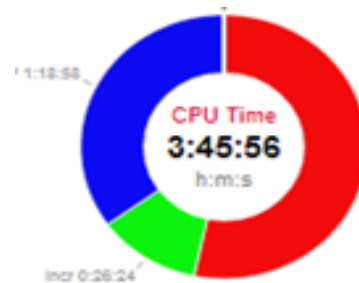
Common User Interface



Improved ease of use and designer productivity

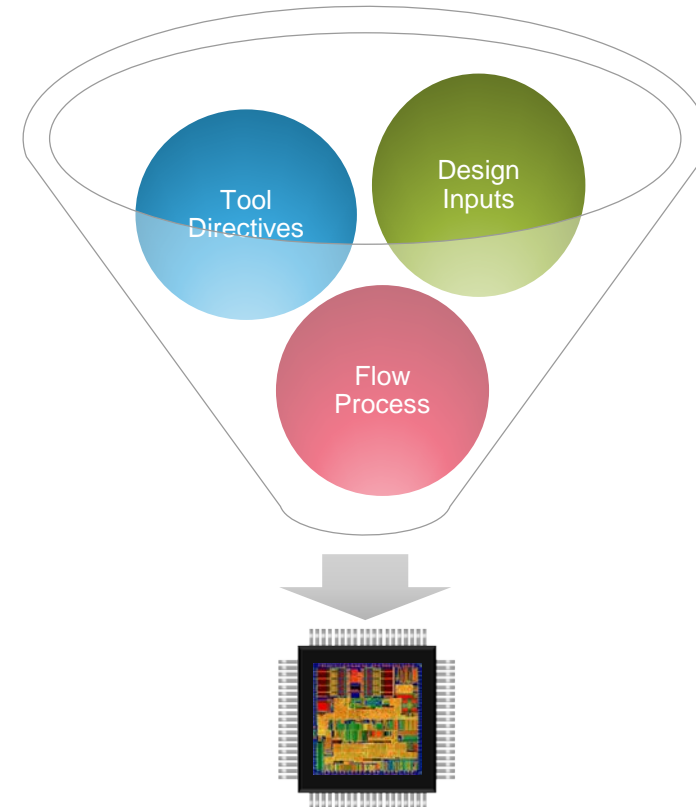
Unified Metrics

	comp	goit
Tool Version:	14.20-0091_1	14.20-0091_1
Machine:	sjfqos004	sjfqos006
Machine Load:	13.89	13.68
User:	user1	user1
Setup Timing		
WNS (ns)	-2.306	-2.442
TNS (ns)	-11.580	-166.631
FEPS:	37	1047
WNS Reg2Reg (ns)	-1.877	-0.910
TNS Reg2Reg (ns)	-7.172	-1.682
FEPS Reg2Reg:	33	9
Hold Timing		
WNS (ns)	-0.381	-0.316
TNS (ns)	-2653.757	-2788.974
FEPS:	21615	26669
WNS Reg2Reg (ns)	-0.178	-0.225
TNS Reg2Reg (ns)	-2291.131	-2374.046
FEPS Reg2Reg:	17238	20945
DRV Violations		
Tran:	12	24
Cap:	0	0
Fanout:	1	0
Density:	0.4	0.4
# Instances:	2297569	2491814
# Buffer:	224356	341765
# Inverter:	168956	244684
# Sequential:	90842	90842
Physical		
Total Area (um ²):	6467808.06	5993161.42
Buffer Area (um ²):	236965.99	473254.81
Inverter Area (um ²):	103490.95	249874.31
Sequential Area (um ²):	334016.78	341310.67
Routing		
# of Layers:	11	11
Routing Wirelength (um):	306285034.000	134865270.000
Runtime		
CPU (s):	138.29.52	250.46.20
Walltime (s):	54.46.53	85.58.22
Memory		
Resl + VirtMem:	64282	76592
Peak Resl:		



Consistent PPA reporting across the whole digital flow

Flow Capture and Automation



Quickly capture digital flows and deploy to users

Joules™
RTL Power Analysis

Genus™
Synthesis

Modus™
DFT

Conformal™
LEC

Innovus™
Implementation

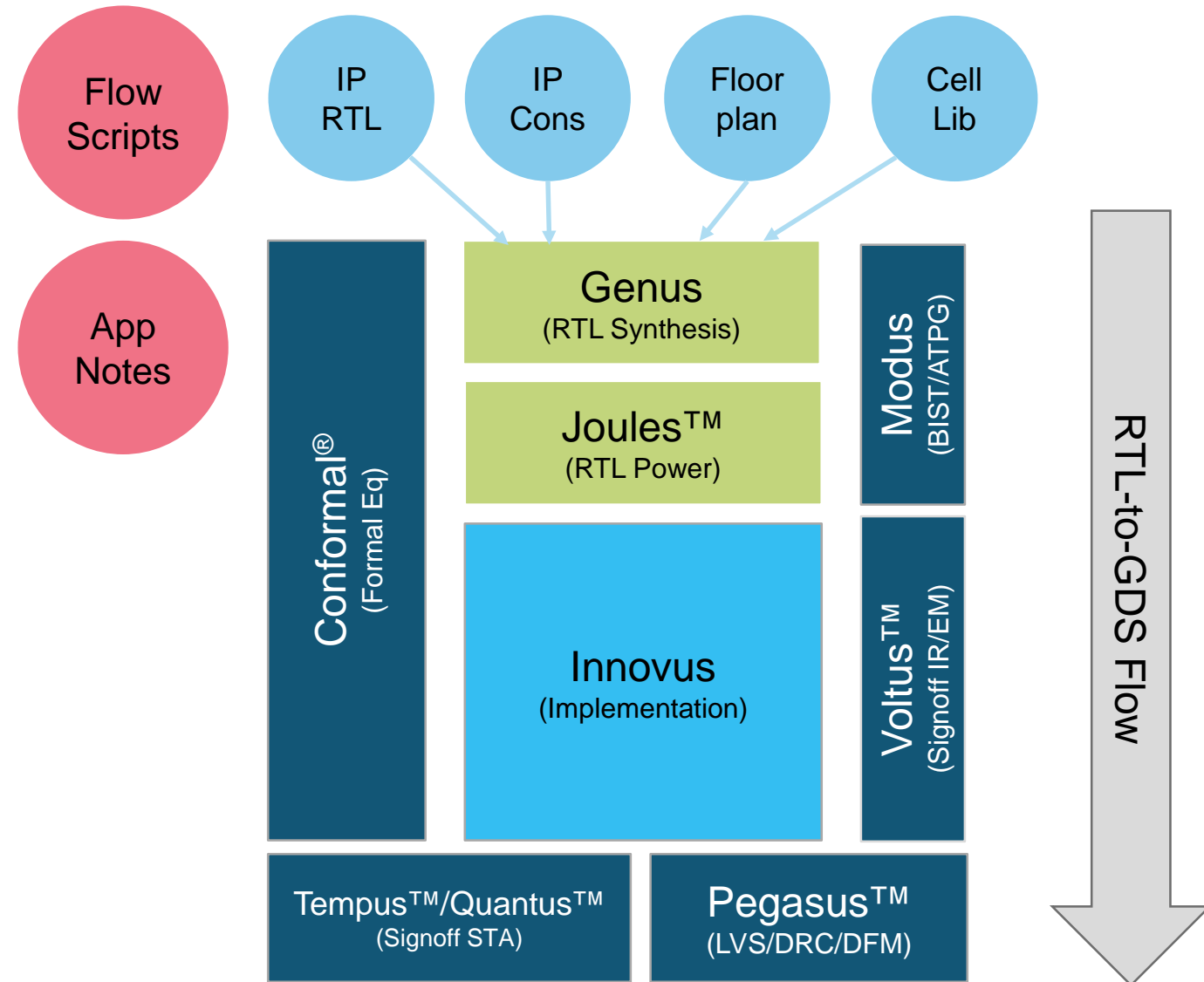
Quantus™
Extraction

Tempus™
Timing

Voltus™
Power

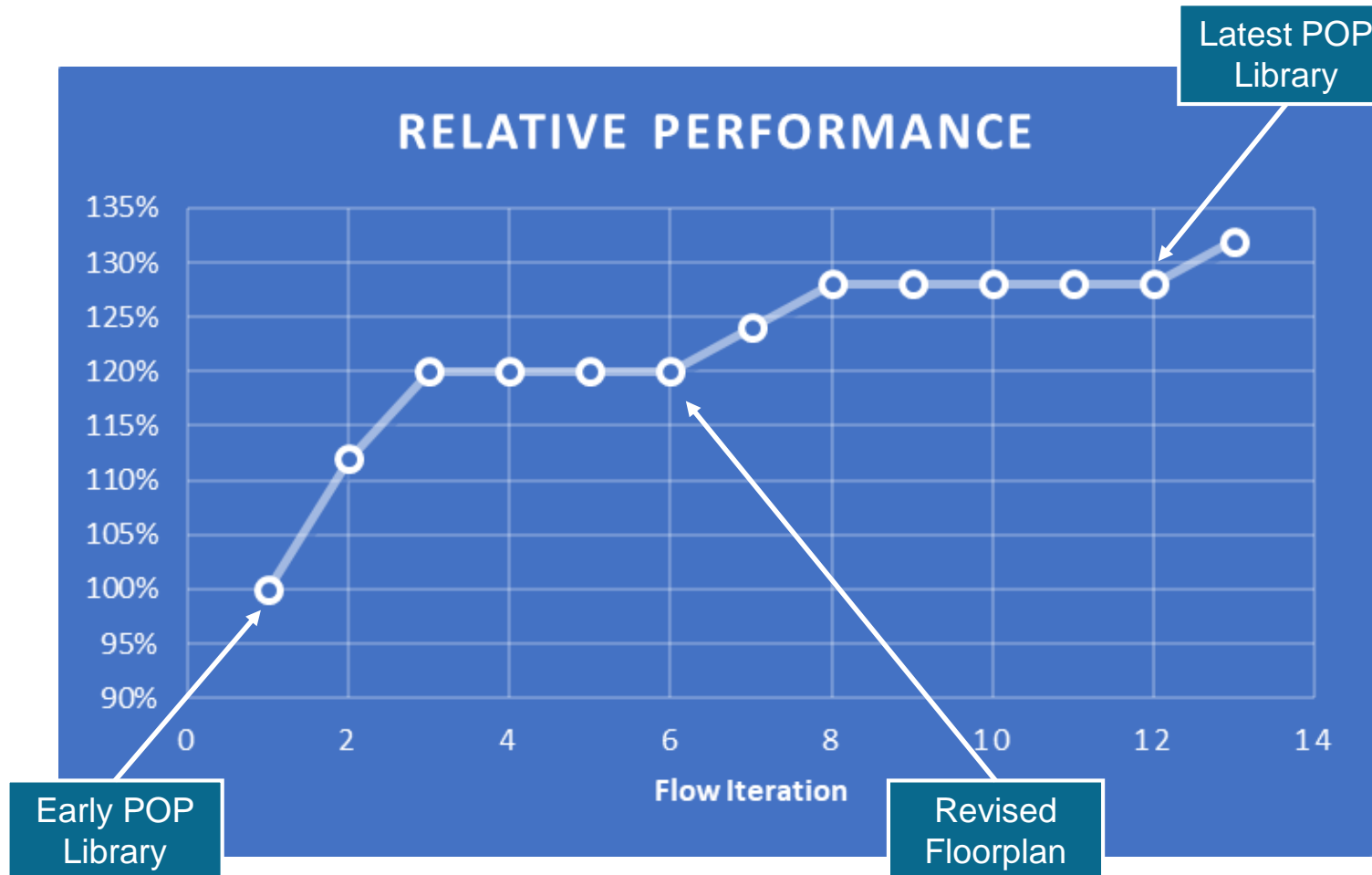
Pegasus™
Verification

Arm CPU 5LPE High-Performance Rapid Adoption Kit



- Complete Cadence RTL-to-GDS digital implementation flow
 - Example flow scripts
 - Example floorplan
 - Application note explaining how to setup the RAK
 - Application notes showing how the flow works
- Customized for latest advanced Arm CPU and Samsung Foundry 5LPE process
- Available to customers enabling fast implementation of latest Arm CPU

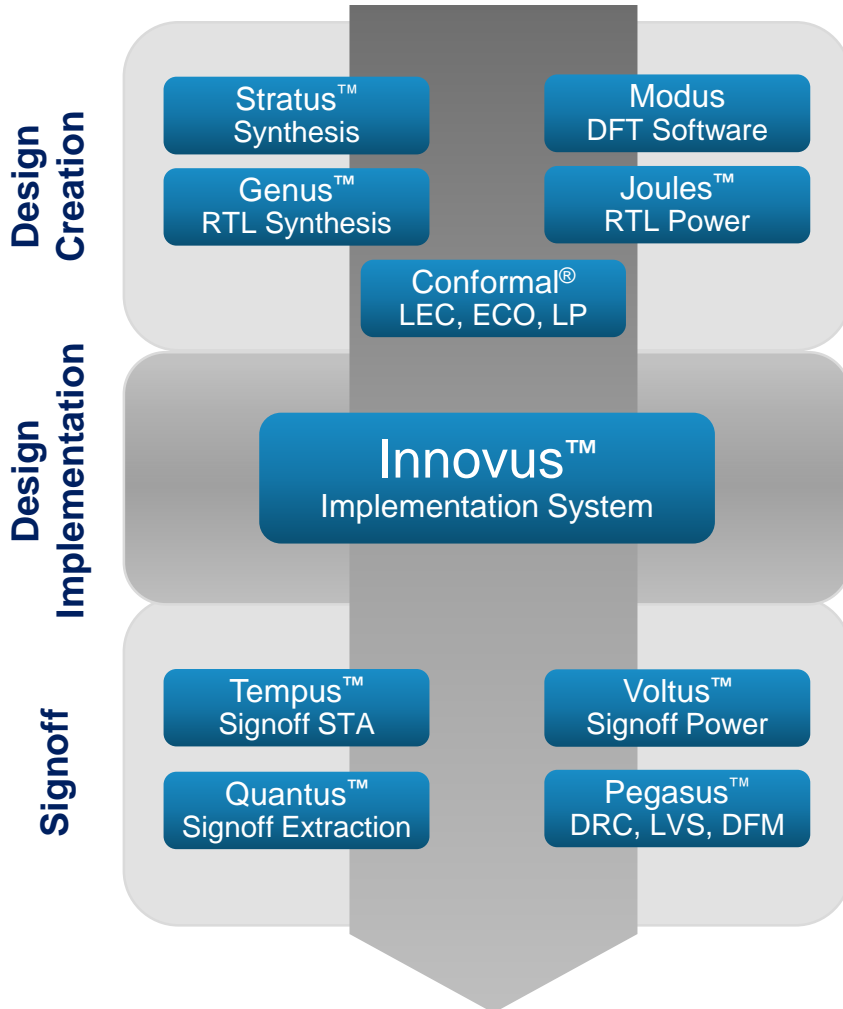
Arm Advanced CPU 5LPE High-Performance RAK Results



- Arm, Samsung Foundry, and Cadence working together have enabled over 30% performance improvements
- More to come as collaboration continues
- Customers have immediate access to improved results using RAK

Over 30% performance improvement achieved so far .. More to come

Delivering Design Excellence for 5LPE Arm CPU Implementation



- Complete Cadence high-performance digital implementation and signoff flow
- Fully qualified for Samsung Foundry 5LPE
 - 5LPE process and tool co-optimization
 - One simple command to enable 5LPE set-up
 - 5LPE Statistical Via Timing Analysis and Optimization
- Tuned and proven on Arm high-performance CPU and POP library for outstanding PPA
- Common user interface and FlowKit included as part of Rapid Adoption Kit

arm

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